

**Amendments to the Claims:**

This listing of claims will replace all prior versions, and listings, of claims in the application.

**Listing of Claims:**

1. - 9. (canceled)

10. (previously presented) The device of claim 16, wherein the spatial light modulator is a liquid crystal display (LCD), digital mirror device or deformable mirror device.

11. (previously presented) The device of claim 16, wherein an optical projection system is arranged between the spatial light modulator and the mold holder.

12. (previously presented) The device of claim 16, wherein the mold holder and the spatial light modulator are arranged close to each other without intervening optical means between them.

13. (previously presented) The device of claim 16, wherein a diffuser element is arranged in the path of the exposure beam between the spatial light modulator and the mold holder.

14. (currently amended) The device of claim 16, claim 11, wherein the mold holder is arranged at such distance from the optical projection system that the photoresist layer on the mold to be exposed is outside the focus plane of the optical projection system.

15. (previously presented) The device of claim 16, wherein the spatial light modulator is coupled to a computer, which supplies data about the exposure pattern to be formed in the photoresist layer.

16. (currently amended) A device for exposing, to a predetermined pattern of exposure radiation during a predetermined time, a photoresist layer on a mold surface of a mold having a base shape, the device comprising:

    a radiation source for emitting UV radiation,  
    optical means for concentrating the emitted radiation [[in]] into  
    an exposure beam in a photolithographic process,  
    a spatial light modulator configured to impart to the exposure beam a radiation distribution according to the predetermined pattern and render the photoresist layer developable to selectively remove photoresist material according to the radiation pattern and shape the exposed surface of the layer to a required end shape of the mold, and  
    a mold holder arranged in the path of the radiation from the spatial light modulator for holding the mold to be exposed,  
    whereby wherein the base shape of the mold is configured to be modified to obtain the required end shape of the mold surface further in response to a hot flow development wherein (i) the mold with the exposed patterned photoresist layer is heated to a predetermined temperature to make unexposed photoresist of the exposed patterned photoresist layer fluid and (ii) fast spinning the mold to remove the fluid unexposed photoresist.